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Refining anodic and cathodic dissolution mechanisms: Combined AESEC-EIS applied to Al-Zn pure phase in alkaline solution

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Abstract

In this work, the use of atomic emission spectroelectrochemistry (AESEC) coupled to 14 electrochemical impedance spectroscopy (EIS) is presented as a method of revealing dissolution 15 mechanisms. To illustrate the method, the dissolution kinetics of Al cations from an Al-Zn pure 16 phase (Zn-68 wt.% Al) was investigated in an alkaline solution. In the cathodic potential domain, 17 a nearly direct formation of dissolved Al^{3+} was observed, while in the anodic potential domain 18 the Al dissolution occurred by migration across a $ZnO/Zn(OH)_2$ film. The localization of the 19 charge transfer mechanism depending on applied potential could be distinguished by comparing 20 the DC and AC faradaic yield using AESEC-EIS. 21

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23 Introduction

Since its introduction to the corrosion field by Epelboin *et al.* [1], electrochemical 24 impedance spectroscopy (EIS) has proven itself an essential and ubiquitous technique in 25 corrosion research. For steady state corroding systems, the EIS spectrum may in some cases be 26 used to estimate the corrosion rate of the material without significant electrochemical 27 perturbation of the system [1], and the EIS spectrum itself is often considered as a fingerprint for 28 specific mechanisms revealing different kinetic processes over a wide range of time constants [2]. 29 The difficulty of EIS alone is the inability to identify the specific faradaic reactions that occur 30 during charge transfer. This has given rise to the development of a variety of couplings such as 31 EIS – Raman spectroscopy [3]. The modulated Raman emission signal allows one to "tune in" to 32 surface chemical bonds that form and dissipate in resonance with the modulated electrochemical 33 potential. The theoretical development of such techniques has been addressed in the development 34 of a generalized EIS transfer function [4]. 35

Atomic emission spectroelectrochemistry (AESEC) provides a direct measurement of 36 elemental dissolution rates [5]. One of the difficulties of this technique is that dissolution may be 37 directly related to a faradaic process, weakly related as in the case of anodic dissolution by way 38 of an oxide intermediate, or unrelated as when dissolution is due to a non-faradaic process. The 39 correlation of electrochemical current transients with dissolution transients is one means of 40 distinguishing between these possibilities as demonstrated by Jiang et al. [6, 7] for the dissolution 41 of Zn in the presence of conversion coatings. The coupling of EIS and AESEC allows for a more 42 sophisticated analysis of dissolution kinetics: the oscillating elemental dissolution rates may be 43 related to the oscillating current and the EIS data may be decomposed into elemental components 44 at least for the low frequencies. In this way, the EIS measurement may be obtained on an element 45

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by element basis with the advantage that dynamic systems may be treated directly, by analyzing 46 data in the time domain. A detailed model for AESEC-EIS was developed by Shkirskiy and Ogle 47 [8], directly correlating the elemental dissolution rate and electrical current for pure Zn at open 48 circuit potential. Zn dissolution in 0.1 M NH₄Cl occurred without any significant intermediate 49 film formation as evidenced by the Zn dissolution rate being in-phase with the alternating current 50 (AC) component of the electrical current. In 0.5 M NaCl solution, no correlation between the AC 51 and the Zn dissolution rate was observed, indicating that oxide film formation and dissolution 52 were decoupled faradaic and non-faradaic processes, respectively. The goal of this article is to 53 extend the previous work to a multi-element system and to use the EIS spectra to distinguish 54 different mechanisms of dissolution by taking advantage of the time-resolved measurement of 55 each element of a multi-element system that AESEC technique provides. 56

The Al-Zn alloy system in alkaline solution was considered an ideal system for an early 57 demonstration of the method. The system is industrially significant: Al-Zn alloys are commonly 58 used as galvanic coatings on steel and occur as separate phases in Zn containing Al alloys, such 59 as the 6000 series, and are almost always exposed to alkaline solution in their lifetime either 60 during surface treatment by alkaline etching, or during corrosion when the cathodic reaction leads 61 to local pH changes. The mechanisms of anodic and cathodic dissolution of multi-phase Zn-5 wt.% 62 Al alloy coatings on steel were previously investigated [9, 10]. A complex interaction between 63 the Zn and Al was observed, however, interpretation of the mechanisms of these interactions was 64 hindered due to the multi-phase nature of the commercial coating material. Therefore, to simplify, 65 we isolated the chemistry of a single phase: the α -phase of Al-Zn (Zn-68 wt.% Al). The anodic 66 dissolution of Al and Zn were investigated as a function of potential in slightly alkaline (pH = 67

10.1) [11] and alkaline (pH = 12.8) [12] electrolytes. In the latter, the temperature dependence of 68 anodic dissolution was also investigated [13]. 69

In summary of these results, three potential domains were identified where the dissolution 70 of the material occurred by very different mechanisms. Based on the individual Zn and Al 71 dissolution rate results and the electrochemical current, it was found that Al underwent a direct, 72 potential independent dissolution mechanism in the cathodic potential domain by reacting with 73 H₂O, and without the formation of a significant intermediate oxide film. Metallic Zn accumulated 74 on the surface in a mechanism of cathodic dealloying. In the anodic domain, Zn was transformed 75 into an oxide film and Al dissolution occurred by ionic transfer across the film. As the two 76 mechanisms are very different, it was felt that EIS coupled to AESEC might further confirm 77 these mechanisms and allow a higher degree of precision on the mechanistic details. 78

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Results and discussions 80

Overview of Al₅₂Zn mechanisms as a function of potential 81

The sensitivity of the Al-Zn dissolution mechanism to potential is evident from the 82 AESEC-linear sweep voltammetry (AESEC-LSV) curve of Al_{5.2}Zn (Zn-68 wt.% Al) phase in 0.1 83 M NaOH solution, shown in Fig. 1. Elemental dissolution rates (j_M) and the convoluted electrical 84 current density (j_e^*) as a function of potential are given with 0.5 mV s⁻¹ scan rate. As previously 85 described, the polarization curve clearly shows three potential domains, to which can be ascribed 86 three unique mechanisms of dissolution. The cathodic dealloying domain occurs between -1.72 V 87 to -1.35 V vs. Hg/HgO. It is characterized by an intense Al dissolution rate, $\boldsymbol{j}_{Al}\!,$ and a Zn 88

dissolution rate, j_{Zn} , close to the detection limit. A direct reaction between Al and H₂O was inferred with significant hydrogen evolution reaction (HER) [14] and accumulation of metallic Zn.

$$AlZn_{r} + 4H_{2}O + e^{-} \rightarrow Al(OH)_{4} + xZn(s) + 2H_{2}(g)$$
^[1]

Al dissolution rate was potential independent and in fact, did not reflect or correlate in anyway
 with the electrochemical current the magnitude of which was much lower and changed sign
 during this potential domain.

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Fig. 1. Elemental AESEC-LSV curve of $Al_{5,2}Zn$ phase in 0.1 M NaOH, pH=12.80, Ar deaerated electrolyte at T = 25 °C. All potential values presented in this work are referenced to an Hg/HgO electrode in 0.1 M NaOH (-165 mV vs. SHE). Vertical dashed lines are selected potential values in the (a): cathodic dealloying, (b): anodic and (c): intermediate domains.

A totally different mechanism is apparent in the anodic domain (from -0.9 V to -0.4 V vs. 102 Hg/HgO), evidenced by the nearly congruent dissolution of Zn and Al, and the significantly 103 decreased amplitude of perturbations in the j_{Al} signal. The DC faradaic yield of elemental 104 dissolution may be determined as $\eta_{DC} = j_{\Sigma} / j_{e}^{*}$ when cathodic current contribution is negligible, 105 where $j_{\Sigma} = j_{Zn} + j_{Al}$. In this case, the dissolution rate follows the electrical current with nearly a 106 100% DC faradaic yield (η_{DC} = 0.98) of dissolution. The potential independence of Zn and Al 107 dissolution rates suggests an oxide film formation type of mechanism and indeed, Raman 108 spectroscopy and SEM analysis also demonstrated the formation of ZnO layer in this potential 109 domain [11, 12] 110

The elemental dissolution rates in the *intermediate domain* (from -1.35 V to -0.90 V vs. Hg/HgO), is more complex and involves the accumulated metallic Zn enriched layer, Zn(0), that was formed in the cathodic domain by the preferential Al dissolution. At the onset of Zn dissolution, there is a notable decrease in the j_{Al} , that we previously termed a *negative correlation effect* (NCE) in [12]. The j_{Zn} reached its maximum value in approximately the same potential domain as j_{Al} obtained its minimum value.

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118 **AESEC-EIS results**

To corroborate and gain further insight into the proposed dissolution mechanisms, potentiostatic EIS was performed simultaneously with AESEC in the three potential domains, at potentials indicated as (a), (b), and (c) in **Fig. 1**. The Nyquist plots are presented in **Fig. 2** and the corresponding AESEC-EIS dissolution profiles are given in **Figs.** 3A - 3C. The effective oxide

- 6 -

¹²³ capacitance (C_{δ}) values determined by the complex capacitance curve [15], the constant phase ¹²⁴ element (CPE) parameters (α and Q), and the corresponding effective oxide layer thicknesses (δ) ¹²⁵ for each potential domain are summarized in **Table 1**.

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127 The Cathodic Dealloying Domain (-1.72 V to -1.35 V vs. Hg/HgO)

EIS in the cathodic dealloying domain (**Fig. 2A**) revealed a single time constant suggesting that H_2O reduction reaction was the dominating charge transfer reaction. The dissolution profile obtained by AESEC (**Fig. 3A**) again demonstrates the potential independence of Al dissolution, as the potential cycles at low frequency do not appear as oscillations in the elemental dissolution rates. This is an important conclusion because it indicates that the EIS spectra are revealing information on the interfacial electrochemical processes that may not directly affect the dissolution rate.



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Fig. 2. Nyquist plots at each potential domain determined from Fig. 1 and their corresponding
 SEM images; A: -1.70 V vs. Hg/HgO, B: -0.80 V vs. Hg/HgO and C: -1.20 V vs. Hg/HgO. Arrows
 are indicating frequency values (Hz).

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Fig. 3. AESEC-EIS curve of $Al_{5,2}Zn$ in 0.1 M NaOH, Ar deaerated electrolyte including potentiostatic hold (E_{ap}) , EIS and open circuit measurement (E_{oc}) . A: $E_{ap} = -1.70$ V vs. Hg/HgO, **B**: $E_{ap} = -0.80$ V vs. Hg/HgO and **C**: $E_{ap} = -1.20$ V vs. Hg/HgO. j_M (M = Zn or Al) values are normalized based on the molar composition for **B** and **C**.

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The analysis of the high frequency loop shows a CPE behavior where $\alpha = 0.73$ and Q = (1.07 ± 0.20) x 10⁻³ Ω^{-1} cm⁻² s^{α -1}, estimated from a graphical analysis [16]. Assuming that this time constant is attributed to a 2D frequency distribution [17], Brug's relationships [18] allow an estimation of the equivalent capacitance from the CPE parameters, in this case the double layer capacitance, C_{dl} = 191 μ F cm⁻². This value is about an order of magnitude larger than the expected value for a double layer capacitance and could represent the response of a very thin, perhaps a non-uniform oxide film. It is reasonable to suppose that Al(OH)₃ forms as a short lived intermediate in Reaction 1 as previously discussed [12, 13]. Reaction 1 may be broken down into
 more elementary steps as follows:

$$3H_2O + 3e^- \rightarrow 3/2 H_2 + 3OH^-$$
 [2]

152

151

$$AlZn_{x} + 3OH^{-} \rightarrow Al(OH)_{3} + xZn(s) + 3e^{-}$$
[3]

153

$$Al(OH)_3 + OH^- \rightarrow Al(OH)_4^-$$
[4]

AESEC directly measures Reaction 4, which involves no electron transfer and in principle should 154 be potential independent. The EIS results indicate that water reduction was potential dependent 155 (Fig. 2A). This confirms the conclusions of [13]; the dissolution of Al oxide/hydroxide layer 156 (Reaction 4) was the rate determining step (RDS) in accordance with previous studies [19, 20, 21, 157 22]. At steady state, Reactions 3 - 4 must occur at identical rates. The properties of the film most 158 likely determine the reaction rate by controlling the access of H₂O to Al metal. The presence of 159 the film may not be directly detected by AESEC due to the intense dissolution rate and cathodic 160 current, however, the film is detected indirectly by EIS. The cathodic current resulting from the 161 HER may be determined simply as $j_{\Delta} = j_e^* - j_{\Sigma} = j_c$, shown in **Fig. 3A**. 162

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The anodic domain (-0.9 V to -0.4 V vs. Hg/HgO)

In the anodic domain, the polarization curve (**Fig. 1**) demonstrates that Zn and Al dissolution rates and the electrochemical current are stable and nearly independent of potential. In the EIS spectrum (**Fig. 2B**), three-time constants are observed. The high frequency capacitive loop may be attributed to the charge transfer resistance of Zn and / or Al oxidation in parallel with the interfacial capacitance. In this system, independent anodic dissolutions from Zn and Al simultaneously occur at different rate and thus the admittance is the sum of these contributions. This may explain why the two entangled time constants are observed in the high frequency domain. The low frequency loop shows a nearly 45° phase that suggests a diffusion process [23, 24]. The time constant observed at intermediate frequency (approximately f = 1 Hz) is poorly resolved due to overlap with the high and low frequency contributions and will not be discussed.

The high frequency capacitive loop is flattened and this can be described by a CPE in 175 parallel with the charge transfer resistance. We assume that this CPE is due to the distribution of 176 properties in a thin oxide film [16], for instance, the distribution of resistivity according to a 177 power-law model [25, 26]. From the analysis of the complex capacitance calculated from the 178 impedance data [15], the high frequency limit of the of the capacitance was $C_8 = 0.65 \pm 0.05 \ \mu F$ 179 cm⁻². Such a low value is characteristic of the dielectric response of a thin oxide film. Assuming a 180 dielectric constant $\varepsilon = 8.8 \pm 0.8$ for ZnO [27] the thickness of the thin oxide film, δ , formed at the 181 electrode interface is given by; 182

183

$$\delta = \varepsilon \varepsilon_0 / C_{\delta}$$
 [5]

where ε_0 is the vacuum permittivity (8.85 x 10⁻¹⁴ F cm⁻¹). This equation yields $\delta = 12 \pm 1$ nm. Such a value confirms the hypothesis that the interfacial capacitance is governed by the thin oxide film contribution (*i.e.* the double layer capacitance which is in series with the capacitive contribution of the oxide film, has in this case a negligible contribution).

The presence and characteristics of the oxide film may be further refined by consideration of the low frequency capacitive loop. For the AESEC-EIS (**Fig. 3B**), very slight oscillations are observed in the Zn and Al dissolution rate at low frequency (magnified curve is given in the ¹⁹¹ inset). The faradaic yield of dissolution for the total current, $\eta_{DC} = 0.96 \pm 0.03$ close to 1, in ¹⁹² agreement with [12]. The faradaic yield of the AC component, η_{AC} , is defined as:

[6]

[7]

¹⁹³
$$\eta_{AC} = AC \text{ amplitude } (j_{\Sigma}) / AC \text{ amplitude } (j_{e}^{*})$$

From the data in **Fig. 3B**, $\eta_{AC} = 1.01 \pm 0.05$, reasonably identical to η_{DC} within experimental error. Note that error bar of η_{AC} was obtained from different frequency domains. It appears to be distributed essentially in the Al dissolution although slight peaks above background are observed for Zn dissolution as well.

The second capacitive loop in **Fig. 2B** shows a typical diffusion-controlled charge transfer mechanism through an oxide layer [24]. Interestingly, the characteristic frequency, $f_{c_{s}} = 0.032$ Hz at the apex of the time constant of the diffusion process in the Nernst layer may be expressed as;

$$f_{\rm c} = 2.51 \text{ D} / 2\pi \delta^2$$

where δ is the thickness of the corrosion product, that can be in a first approximation evaluated to 202 be at least the thickness previously obtained from the CPE parameter ($\delta = 12$ nm). The diffusion 203 coefficient may be calculated from Eq. 7, $D = 1.15 \times 10^{-13} \text{ cm}^2 \text{ s}^{-1}$. Such a low value should be 204 due to the underestimated δ value because the calculation did not consider the porosity of the 205 oxide as well as the accumulation of corrosion products at the electrode surface. It may be 206 attributed to a diffusion of species inside of a micrometric diffusion layer of corrosion product. In 207 this case, the diffusion and migration caused by the large electric filed inside the film should be 208 taken into account. 209



B. $E_{ap} = -1.20$ V vs. Hg/HgO

Fig. 4. The oscillation trends at low frequency domain for A: $E_{ap} = -0.80$ V vs. Hg/HgO and B: $E_{ap} = -1.20$ V vs. Hg/HgO from Figs. 3B and 3C, respectively.

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Fig. 4 shows the oscillation trends of the j_e , j_e^* , j_M and applied potential (E) at a given frequency of AESEC-EIS result from Fig. 3. To facilitate the comparison, each profile is presented in arbitrary units. The phase shift of j_M and j_e^* vs. E (ϕ_{j_M}) results from the residence time distribution of the flow cell [5], which means that it is not frequency dependent but time dependent. The actual phase shift between E and j_e (ϕ) was nearly zero in all cases as shown in **Fig. 4**.

The impedance contribution from each elemental dissolution in real part, Z_r (j_M), is given in **Table 2**, calculated at each frequency domain as:

$$Z_{r}(j_{M}) = (|d E| / |d j_{M}|) \cos(\phi)$$
[8]

For $E_{ap} = -0.80$ V vs. Hg/HgO (**Fig. 4A**), j_{Zn} oscillation is less evident than at $E_{ap} = -1.20$ V vs. 221 Hg/HgO (Fig. 4B), probably indicating a weak potential dependent Zn dissolution in the anodic 222 potential domain due to the Zn-based corrosion products formation. The high $Z_r (j_{Zn})$ values at 223 E_{ap} = -0.80 V vs. Hg/HgO could also be explained by the weak potential dependency of Zn 224 dissolution at this potential. For $E_{ap} = -1.20$ V vs. Hg/HgO, $Z_r (j_{Zn}) + Z_r (j_{Al}) \approx Z_r - R_e$, which may 225 indicate that j_{Zn} and j_{Al} contributed to the total impedance with a parallel relationship. Note that 226 Z_r is measured by potentiostat then subtracted by the electrolyte impedance, $Z_e = R_e$. It is 227 consistent with the previously proposed dissolution model of the Al_{5.2}Zn phase in which Al 228 dissolution occurred through a porous Zn(0) layer in parallel with Zn dissolution [12]. It should 229 be mentioned that the dissolution is not a simple mechanism as it usually involves the adsorbed 230 intermediate species which may result in a delay between the j_e^* and j_M . 231

The correlation between the AC current and dissolution rates is highlighted by the Lissajous analysis in **Figs. 5A** ($E_{ap} = -0.80$ V vs. Hg/HgO) and **5B** ($E_{ap} = -1.20$ V vs. Hg/HgO) at f = 0.004 Hz. j_e^* curve is shown on the top, both for upper and lower potential scans. For j_M vs. E

235	curves in the middle, j_e^* assuming congruent dissolution of Al and Zn are also shown. For
236	example in Fig. 5A , Al dissolution was congruent as $j_{Al} \approx (j_e^* / 1.13)$ whereas Zn dissolution was
237	not as $j_{Zn} < (j_e^* / 8.8)$. The correlation of Zn dissolution rate with potential is less obvious than for
238	Al, but exists (also see Fig. 4A). In principle, at this potential, there is no significant cathodic
239	reaction, so we conclude that the AC current is primarily going to the formation and reduction of
240	ZnO or Zn(OH) ₂ . It was previously shown that the $\eta_{AC} \approx \eta_{DC} \approx 1$ at $E_{ap} = -0.80$ V vs. Hg/HgO,
241	supporting this assumption. The weak correlation is interesting since the overall faradaic yield of
242	dissolution based on the DC current density and elemental dissolution rates was nearly 100%
243	$(\eta_{DC} = 0.96 \pm 0.03)$ at this potential. In this case, it could be concluded that the DC component
244	was due to the dissolution of the corrosion products [6, 7, 28].

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Fig. 5. Lissajous analysis at f = 0.004 Hz at A: $E_{ap} = -0.80$ V vs. Hg/HgO and **B**: $E_{ap} = -1.20$ V vs. HgO. The j_e^* , j_{Al} and j_{Zn} are shown as a function of IR drop compensated applied potential (E- $j_e R_e$). One cycle including upper and lower potential scans, indicated by arrows, is given.

The kinetic parameters for ZnO formation and reduction may be estimated from the j_{Δ} vs. E Lissajous plot, shown in the bottom of **Fig. 5**. The Zn dissolution in the anodic potential domain (**Fig. 5A**) may be the combination of a series of elementary reactions as:

$$Zn + 2OH^{-} \rightarrow Zn(OH)_{2} + 2e^{-}(j_{\Delta})$$
[9]

$$Zn(OH)_2 + OH^- \rightarrow Zn(OH)_3^-$$
[10]

$$Zn + Zn(OH)_2 + 2OH^- \rightarrow 2ZnO + 2H_2O + 2e^-(j_{\Delta})$$
[11]

$$ZnO + OH^{-} + H_2O \rightarrow Zn(OH)_3^{-}(j_{Zn})$$
[12]

The intermediate species such as ZnOH or ZnOH_{ads} [29, 30, 31] are not considered as the time scale of the AESEC experiment is too slow to measure these species. The formation rate of Zn(OH)₂ or ZnO (j_{Δ}) is potential dependent (Reactions 9 and 11) given that the Lissajous plot of j_{Δ} vs. E showed the linearity, neglecting the contribution of cathodic current at this potential. The anodic Tafel slope of j_{M} ($b_{a, j_{M}}$) may be calculated as;

$$b_{a, j_M} = 2.303 \Delta E / \ln(j_M^+/j_M^-)$$
 [13]

where j_{M}^{+} and j_{M}^{-} are j_{M} values measured at the highest and lowest potential, respectively. ΔE is the difference between the highest and lowest potential. $b_{a, j_{\Delta}} = 94 \text{ mV}$ decade⁻¹ and $b_{a, j_{Zn}} = 2350$ mV decade⁻¹ are calculated by Eq. 13. It is clearly demonstrated that the formation of ZnO (Reaction 11) is faster than the dissolution (Reaction 12), resulting in the growth of the ZnO layer [12, 13].

The quantity of oxide formed during the AESEC-EIS experiment may be estimated by the 275 dissolution profile obtained after releasing the potential to open circuit at the end of the 276 experiment. The $E_{ap} = -0.80$ V vs. Hg/HgO AESEC-EIS profile of **Fig. 3B** illustrates this idea. At 277 the end of the experiment, the presence of oxide dissolution is indicated by a plateau in the E_{oc} vs. 278 time profile at approximately E_{oc} = -1.50 V vs. Hg/HgO. The removal of the oxide and the 279 exposure of the underlying metallic substrate is indicated by the sudden drop in potential to < -280 1.6 V vs. Hg/HgO. The removal of the oxide film gives rise to a transient dissolution of Zn, 281 which decays steadily but at a rate significantly slower than the residence time distribution 282 associated with the flow cell. The latter is indicated by the drop of the convoluted 283 electrochemical current, j_e^* . Integration of the j_{Zn} yields a thickness of ZnO layer $\delta = 11$ nm was 284 obtained assuming a uniform ZnO layer formation over the geometrical surface area and a ZnO 285 density of 5.6 g cm⁻³. This is in the same range as the thickness estimated from EIS of 12 ± 1 nm 286 (Table 1). 287

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The Intermediate Domain (-1.35 V to -0.9 V vs. Hg/HgO)

In the intermediate domain, both j_{Zn} and j_{A1} showed clear in-phase oscillations, with the low frequency AC current (**Fig. 3C**). The EIS response in **Fig. 2C** shows three capacitive time constants and one inductive loop. An inductive loop has already been reported for both Zn and Al dissolution. In the case of Zn, this loop is usually observed in the intermediate frequency range [24, 32] whereas for Al, it can be only be seen in the low frequency domain in an alkaline solution [33, 34]. We thus conclude that the inductive loop observed for $f < 10^{-2}$ Hz may be attributed to the relaxation of the surface intermediates involved in the dissolution mechanism of Al and Zn [35]. The third capacitive loop is similar to the one observed at $E_{ap} = -0.80$ V vs. Hg/HgO and may be ascribed to diffusion processes inside a thin layer. The characteristic frequency is also similar to the previous case in **Fig. 2B** confirming that convection-diffusion controlled mechanism by the flux of the electrolyte in the AESEC experiment.

³⁰¹ The second capacitive loop $(10^{-1} \text{ Hz} < f < 10^{0} \text{ Hz})$ was also distributed and its analysis is ³⁰² complicated by the fact that it is convoluted with other processes at both higher and lower ³⁰³ frequency. However, it may be ascribed to Zn dissolution [24]. The high frequency time constant ³⁰⁴ was analyzed as previously described. From the CPE behavior, the oxide film thickness was ³⁰⁵ estimated at $\delta = 2.4$ nm. The analysis of the high frequency loop for each potential showed that ³⁰⁶ the thin film formed on the alloy surface has a thickness that strongly depends on the applied ³⁰⁷ potential.

In **Fig. 3C**, a peak of Zn dissolution is observed after the potential release, albeit a much smaller peak than at $E_{ap} = -0.80$ V vs. Hg/HgO (**Fig. 3B**). Nevertheless, this peak cannot be unequivocally attributed to oxide dissolution as there is no clearly defined potential plateau following the potential release. Assuming that this peak was due to oxide dissolution, an estimated thickness of 2.5 nm is obtained with the same assumptions as before, in good agreement with that obtained from the EIS analysis of 2.4 ± 0.3 nm (**Table 1**).

The low frequency Lissajous plots at E_{ap} =-1.20 V vs. Hg/HgO (**Fig. 5B**) show linear behavior within experimental error indicating that the elemental dissolution current (j_{M}) for each species is in-phase with the potential. In this case, the linearity of the Lissajous plots of j_{Zn} and j_{Δ} is clearly demonstrated, indicating that both reactions are charge transfer limited. The cathodic current would make a negligible contribution to j_{e}^{*} as E_{ap} was approximately +400 mV than the zero current potential ($E_{j=0}$). The Zn oxidation reaction may be written by the combination of Reactions 9 and 10 as;

$$\operatorname{Zn} + \operatorname{3OH}^{-} \to \operatorname{Zn}(\operatorname{OH})_{3}^{-} + 2e^{-}(j_{Zn})$$
 [14]

and the formation of the ZnO (j_{Δ}) is via Reaction 11. $b_{a, j_{\Delta}} = 68 \text{ mV} \text{ decade}^{-1}$ and $b_{a, j_{Zn}} = 864 \text{ mV}$ decade⁻¹ were obtained by Eq. 13 from **Fig. 5B**. Given that the Tafel slope of j_{Zn} at $E_{ap} = -1.20 \text{ V}$ vs. Hg/HgO is lower than that at $E_{ap} = -0.80 \text{ V}$ vs. Hg/HgO, it could be concluded that the dissolution of Zn is faster in former case resulting in a relatively thinner ZnO layer formation.

In this case, both Zn and Al dissolution were not faradaic in that $j_e^*/1.13 \neq j_{Al}$ and $j_e^*/8.8$ 326 $\neq j_{Zn}$ (Fig. 5B). It showed a significant difference between η_{DC} = 0.92 \pm 0.02 and η_{AC} = 0.65 \pm 327 0.03. It was proposed that the AC component is due to non-faradaic reactions at the metal/oxide 328 interface and the DC component to the faradaic dissolution of the film at the oxide/electrolyte 329 interface [6, 7, 28]. For the AC case in the intermediate domain, it can be concluded that 330 formation of the corrosion product would be the RDS, given that $\eta_{DC} >> \eta_{AC}$, consistent with the 331 Tafel slope analysis. A simplified elemental dissolution at each interface in anodic potential 332 domain is illustrated in Fig. 6. The system extends our previous work with AESEC-EIS in that 333 the potential dependent and potential independent mechanisms are observed for two different 334 elements of a single system. In the previous work they were observed for Zn in different 335 electrolytes [8]. 336

Interestingly, j_{Zn} was higher than its congruent dissolution level ($j_e^* / 8.8$) whereas j_{Al} was lower than $j_e^* / 1.13$. The excess Zn dissolution could lead to a restrained Al dissolution, referenced as the *NCE* [12].

- 21 -

Fig. 6. Simplified schematic model of elemental dissolution at each interface of $Al_x Zn$ in 0.1 M NaOH solution in anodic potential domain.

340

₃₄₁ Al_{0.7}Zn (Zn-22 wt.%Al)

In this section, we will demonstrate the AESEC-EIS methodology with a system that is 342 intrinsically unstable and shows a more usually observed dissolution case for the lower Al 343 content Zn-Al system [36]. An AESEC-EIS curve (Fig. 7A), magnified oscillation trends at f =344 0.010 Hz (Fig. 7B) and a corresponding Nyquist plot (Fig. 7C) for the Al_{0.7}Zn (Zn-22 wt.% Al) 345 nominally pure phase at $E_{ap} = -1.36$ V vs. Hg/HgO (*i.e.* +150 mV from $E_{j=0}$) in the same 346 electrolyte are given. It is clear from Fig. 7A that the elemental dissolution mechanism varies 347 throughout the time period of the experiment. Initially, Zn dissolution was intense at 348 approximately the same level as Al. However, for t > 2700 s (f < 0.005 Hz), j_{Zn} decreased to 349 under the detection limit and Al dissolution changed from a charge transfer to a chemical 350 dissolution mechanism. The latter is indicated by the disappearing oscillation of j_{AI} , and the 351 significantly increased j_{A1} noise signal indicating HER [12, 14]. The non-charge transfer Al 352

dissolution mechanism is also revealed in the Nyquist plot (Fig. 7C) where an unambiguous diffusive impedance trend was observed ($\phi = 45^\circ$) in this frequency domain. ZnO/Zn(OH)₂ formation and dissolution would occur for $f \ge 0.007$ Hz as Reactions 9 - 12:

A.

В.

С.

Fig. 7. A: AESEC-EIS curve of Zn-22 wt.% Al in 0.1 M NaOH, Ar deaerated electrolyte, at E_{ap} = -1.36 V vs. Hg/HgO, **B**: oscillation trends at f = 0.010 Hz, and **C**: corresponding Nyquist plot.

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 j_{Zn} showed a clear oscillation from a relatively higher frequency domain ($f \approx 0.030$ Hz) 357 where no j_{Al} oscillation was observed. j_{Al} oscillation disappeared with the dissolution of 358 $ZnO/Zn(OH)_2$ for t > 2700 s, indicating that Al dissolution occurred through this Zn-based 359 corrosion product layer (see also Fig. 6). The phase shift of E vs. j_e (ϕ) was not zero as 360 summarized in **Table 3**, whereas $\phi \approx 0$ for Al_{5.2}Zn (Fig. 4). The measured total impedance was 361 close to the sum of each elemental contribution calculated from Eq. 8, $Z_r - Z_e \approx Z_r (j_{Zn}) + Z_r (j_{Al})$, 362 similar to the Al_{5.2}Zn in the same potential domain, which can be an indicative of the parallel 363 relationship between Zn and Al dissolution. The phase shift between j_{Zn} and j_{Al} was 180° (Fig. 7B) 364 whereas in-phase relation was monitored for $Al_{5.2}Zn$ (Fig. 4). The out-of-phase of j_{Zn} and j_{Al} 365 should have been explained by the fact that Al dissolution is related to the cathodic reaction at 366 open circuit potential [28]. However, it is not probable in the present work because this phase 367 shift was observed at a relatively positive potential where cathodic current contribution is 368

negligible. One possible explanation is that in this potential domain, the slope of the Al dissolution rate - potential curve is negative [36] resulting in a negative low frequency-impedance
 [37, 38].

For $f \le 0.007$ Hz, j_{Zn} decreased to under the detection limit as all the previously formed ZnO/Zn(OH)₂ dissolves. Previously for Al_{5.2}Zn phase, a clear Zn dissolution peak was observed during the spontaneous dissolution after the AESEC-EIS experiments in **Figs. 3B and 3C**. It was attributed to the residual ZnO/Zn(OH)₂ dissolution formed during the potentiostatic experiment. In **Fig. 7**, no j_{Zn} peak was monitored in E_{oc} indicating that the oxide was completely dissolved near t = 2700 s.

378

379 Conclusion

In this work, we have demonstrated the application of combined AESEC-EIS to identify and quantify different anodic dissolution processes for a multi-element system, Al-Zn pure phase in 0.1 M NaOH. The elemental dissolution mechanism at each potential domain was elucidated by the AESEC-EIS technique.

AESEC gave immediate information on the elemental dissolution rates and transient behavior while EIS gave information on the physical properties of intermediate oxide layers and kinetic information for water reduction in the cathodic domain. A potential independent Al dissolution without forming an oxide layer was observed by AESEC-EIS at a cathodic potential domain ($E_{ap} = -1.70$ V vs. Hg/HgO).

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By comparing the DC and AC faradaic yield, information on the localization of charge 389 transfer reactions could be obtained. In the anodic domain (E $_{ap}$ = -0.80 V vs. Hg/HgO), $\eta_{DC} \approx \eta_{AC}$ 390 indicating that the formation and dissolution of the corrosion products occur at the nearly same 391 rate, consistent with the previous observation [12, 13]. In the intermediate domain ($E_{ap} = -1.20$ V 392 vs. Hg/HgO), formation would be the RDS as $\eta_{DC} >> \eta_{AC}.$ In the former case, the oxidation of 393 metal occurred through a corrosion product layer. In the latter case, the oxidation would occur 394 directly from the metal/oxide complex. It was further demonstrated by the Tafel slope of j_{Zn} from 395 the elemental Lissajous analysis (Fig. 5). In this way, AESEC-EIS can be utilized to distinguish 396 the different elemental dissolution kinetics. Diffusion processes were identified although the 397 precise origin was not ascertained, *i. e.* across corrosion product films or within inter-granular 398 crevices and pits. 399

Elemental impedance contribution, Z_r (j_M), demonstrated the potential dependent elemental dissolution model of Al-Zn pure phase proposed in [12]. In the intermediate potential domain, Al dissolution occur through the porous Zn(0) enriched layer in parallel with Zn dissolution as Z_r (j_{Zn}) + Z_r (j_{Al}) \approx total measured impedance ($Z_r - Z_e$).

For $Al_{5.2}Zn$, Al and Zn dissolution rates were in-phase regardless of the applied potential. For $Al_{0.7}Zn$ and other low Al content alloys and phases [36], Al and Zn dissolution rates showed a 180° phase shift. However, the origin of the phase shift is not ascertained to the satisfactory level.

408

409 Methods

410 Materials

A nominally pure phases of Al-Zn (Zn-68 wt.% Al and Zn-22 wt.% Al), provided and 411 characterized by the Department of Metals and Corrosion Engineering, University of Chemistry 412 and Technology, Prague, were investigated in this work. Zn-68 wt.% Al phase is denoted as 413 Al_{5.2}Zn and Zn-22 wt.% Al as Al_{0.7}Zn, based on their molar compositions to facilitate the 414 congruent dissolution analysis. The chemical composition of these materials were 67.6 wt.% Al 415 and 32.4 wt.% Zn (Zn-68 wt.% Al), and 21.4 wt.% Al and 78.6 wt.% Zn (Zn-22 wt.% Al), 416 respectively, measured by atomic absorption spectroscopy (AAS). All samples were ground with 417 Si-C paper up to P4000 under ethanol, dried with flowing N₂ gas then stored in a humidity 418 chamber of 50% relative humidity with saturated Mg(NO₃)₂ 6H₂O during 24 hours, providing a 419 reproducibly oxidized surface prior to the experiment [36, 39]. All the experiments were 420 performed in a 0.1 M NaOH (pH = 12.80) at T = 25°C, prepared from analytical grade materials 421 using deionized water obtained by a MilliporeTM system (18.2 M Ω cm). The electrolytes were 422 deaerated by Ar gas for 30 min prior to the tests and maintained during the experiments. 423

424

425

Atomic emission spectroelectrochemistry (AESEC)

The AESEC technique has been described in detail elsewhere [5, 40]. The working electrode was in contact with the flowing electrolyte in a specially designed flow cell [5, 41] with conventional three-electrode system; a Hg/HgO in 0.1 M NaOH (-165 mV vs. SHE) as a reference electrode and a Pt foil as a counter electrode. The elements released from the working electrode were transported to an Ultima 2C Horiba Jobin-Yvon inductively coupled plasma atomic emission spectrometer (ICP-AES). The concentrations of Zn and Al were determined

- 27 -

from the emission intensity at 213.86 nm (Zn with a Paschen-Runge polychromator) and at 167.08 nm (Al with a monochromator) wavelength, respectively, using standard ICP-AES calibration techniques.

⁴³⁵ A Gamry Reference 600^{TM} potentiostat was used to perform electrochemical impedance ⁴³⁶ spectroscopy (EIS) and linear sweep voltammetry (LSV). The electrochemical response (namely ⁴³⁷ the electrical current density, j_e, and the electrode potential, E) were recorded in real-time with ⁴³⁸ the elemental dissolution rates, using the analog data acquisition and the software interface ⁴³⁹ (QuantumTM, Horiba Jobin-Yvon) of the AESEC technique. The EIS was performed at different ⁴⁴⁰ potentials from 100 kHz to 0.004 Hz with 8 points per decade of frequency and applying a 10 ⁴⁴¹ mV_{rms} sinewave perturbation.

442

443 Data analysis of the AESEC technique

⁴⁴⁴ The atomic emission intensity at a characteristic wavelength (λ) of the element M, I_{M, λ}, ⁴⁴⁵ was recorded by the ICP-AES as a function of time downstream from an electrochemical flow ⁴⁴⁶ cell. The elemental concentration (C_M) is calculated as;

$$C_{\rm M} = (I_{\rm M,\,\lambda} - I_{\rm M,\,\lambda}^{\circ}) / \kappa_{\lambda}$$
[15]

where $I_{M,\lambda}^{\circ}$ is the background signal, and is κ_{λ} the sensitivity factor of M, obtained from a standard ICP calibration method. The elemental dissolution rate (v_{M}) can be calculated from Eq. 15 with the flow rate of the electrolyte ($f = 2.8 \text{ mL min}^{-1}$) and the exposed surface area A (1.0 cm²) as:

$$v_{\rm M} = f C_{\rm M} / A$$
 [16]

The $v_{\rm M}$ was converted to an equivalent elemental current density $(j_{\rm M})$ to facilitate comparison with the electrical current density $(j_{\rm e})$ measured by the potentiostat, in a relationship with;

$$j_{M} = z F v_{M}$$
 [17]

where F is the Faraday constant and z is the valance of the dissolving species (Al³⁺, Zn²⁺). It is often useful to present j_e^* which represents the measured j_e after a numerical convolution with the residence time distribution in the flow cell (a lognormal distribution), thereby allowing a direct comparison between the instantaneous values of j_e^* and j_M [5]. Cathodic reactions and the formation of insoluble or slightly soluble species are not directly detected by ICP-AES. If surface charging is neglected, the faradaic component of these hidden processes may be determined by a mass-charge balance as:

463

$$\mathbf{j}_{\Delta} = \mathbf{j}_{e}^{+} - \mathbf{j}_{Zn} - \mathbf{j}_{Al}$$
[18]

464

465 Surface characterization

The sample surface after each potentiostatic AESEC-EIS experiment was characterized by scanning electron microscopy (SEM) suing a Zeiss LEO 1530TM microscope with field emission gun source at 15 keV, and with 15 mm working distance. An equal mix of secondary electron and back-scattered electron detector was used.

470

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474 475 476 477 478 479	Author Contributions J. H. carried out the AESEC-EIS experiments and coordinated analysis between two techniques. V. V. was responsible for the EIS data interpretation. K. O. conceptualized the AESEC-EIS analysis. All authors contributed to write the paper and revision.
480	Data availability
481 482 483	The authors declare that the data supporting the findings of this study are available within the paper. The supplementary data will be available upon reasonable request.
484	Competing interests
485	The authors declare no competing interests.
486	
487	
488	Figure captions
489	Fig. 1. Elemental AESEC-LSV curve of Al _{5.2} Zn phase in 0.1 M NaOH, pH=12.80, Ar deaerated
490	electrolyte at $T = 25$ °C. All potential values presented in this work are referenced to an Hg/HgO
491	electrode in 0.1 M NaOH (-165 mV vs. SHE). Vertical dashed lines are selected potential values
492	in the (a): cathodic dealloying, (b): anodic and (c): intermediate domains.

Fig. 2. Nyquist plots at each potential domain determined from Fig. 1 and their corresponding
SEM images; A: -1.70 V vs. Hg/HgO, B: -0.80 V vs. Hg/HgO and C: -1.20 V vs. Hg/HgO.
Arrows are indicating frequency values (Hz).
Fig. 3. AESEC-EIS curve of Al_{5.2}Zn in 0.1 M NaOH, Ar deaerated electrolyte including

⁴⁹⁷ potentiostatic hold (E_{ap}), EIS and open circuit measurement (E_{oc}). **A**: $E_{ap} = -1.70$ V vs. Hg/HgO, ⁴⁹⁸ **B**: $E_{ap} = -0.80$ V vs. Hg/HgO and **C**: $E_{ap} = -1.20$ V vs. Hg/HgO. j_M (M = Zn or Al) values are ⁴⁹⁹ normalized based on the molar composition for **B** and **C**.

Fig. 4. The oscillation trends at low frequency domain for A: $E_{ap} = -0.80$ V vs. Hg/HgO and B: $E_{ap} = -1.20$ V vs. Hg/HgO from Figs. 3B and 3C, respectively.

Fig. 5. Lissajous analysis at f = 0.004 Hz at A: $E_{ap} = -0.80$ V vs. Hg/HgO and B: $E_{ap} = -1.20$ V vs. HgO. The j_e^* , j_{Al} and j_{Zn} are shown as a function of IR drop compensated applied potential (E $j_e R_e$). One cycle including upper and lower potential scans, indicated by arrows, is given.

Fig. 6. Simplified schematic model of elemental dissolution at each interface of $Al_x Zn$ in 0.1 M NaOH solution in anodic potential domain.

Fig. 7. A: AESEC-EIS curve of Zn-22 wt.% Al in 0.1 M NaOH, Ar deaerated electrolyte, at $E_{ap} =$ -1.36 V vs. Hg/HgO, B: Oscillation trends at f = 0.010 Hz, and C: Corresponding Nyquist plot.

Table 1. The effective capacitance values obtained from Brug's relation [18] (a), complex capacitance curve [15] (b) and (c). CPE parameters (α and Q) are provided. The corresponding

effective oxide layer thickness (δ) calculated by Eq. 5 and obtained from the AESEC massbalance are given.

	E _{ap}	С	α	Q	Effective thickness (δ) / nm	
	/ V vs. Hg/HgO	$/ \mu F \text{ cm}^{-2}$		/ Ω^{-1} cm ⁻² s ^{α-1}	EIS	AESEC
(a)	-1.70 V	$C_{dl} = 191$	0.73	$(1.07 \pm 0.20) \ge 10^{-3}$	-	
(b)	-0.80 V	$C_{\delta} = 0.65$	0.78	$(12.6 \pm 0.2) \ge 10^{-4}$	12 ± 1	11
(c)	-1.20 V	$C_{\delta} = 3.3$	0.77	$(4.5 \pm 1.3) \ge 10^{-5}$	2.4 ± 0.3	2.5

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Table 2. The real part impedance measured by the potentiostat $(Z_r - Z_e)$, contribution of Zn dissolution $(Z_r(j_{Zn}))$ and Al dissolution $(Z_r(j_{Al}))$.

f/Hz	$Z_r - Z_e / \Omega \text{ cm}^2$	$Z_{r}(j_{Zn}) / \Omega \text{ cm}^{2}$	$Z_r (j_{Al}) / \Omega \text{ cm}^2$			
$E_{ap} = -0.80 \text{ V vs. Hg/HgO} \text{ (anodic domain)}$						
0.010	194	878	19			
0.004	192	872	61			
$E_{ap} = -1.20 \text{ V vs. Hg/HgO}$ (intermediate domain)						
0.013	305	270	48			
0.010	297	274	37			
0.008	287	275	37			
0.006	279	234	29			
0.004	275	266	34			

f/Hz	$(Z_r - Z_e) / \Omega \text{ cm}^2$	$Z_{r}(j_{Zn}) / \Omega cm^{2}$	$Z_{r}(j_{Al}) / \Omega \text{ cm}^{2}$	φ (E vs. j _e)
0.013	101	61	67	-29°
0.010	103	67	75	-32°
0.007	110	66	28	-63°

Table 3. The real part of impedance, and ϕ obtained from Fig. 7.

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